

Fig.1b  
<Prior Art>



Fig.1c  
<Prior Art>

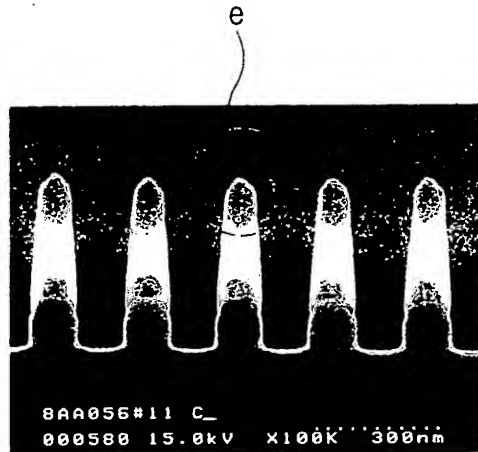


Fig.2c  
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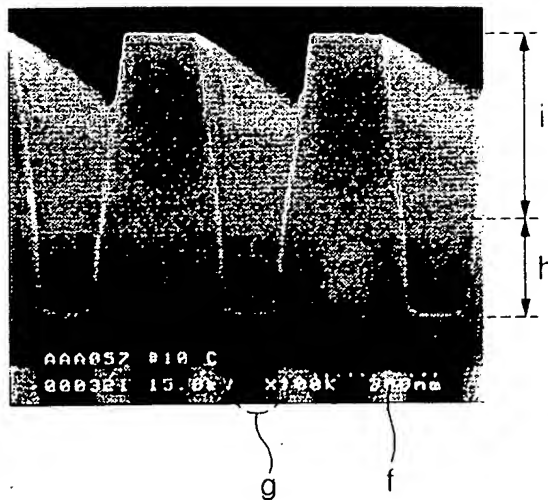


Fig.2d  
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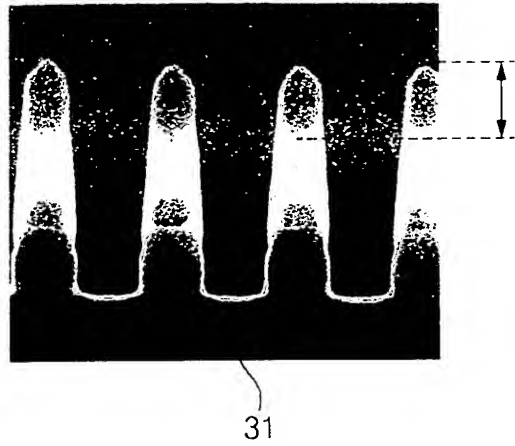


Fig.3a  
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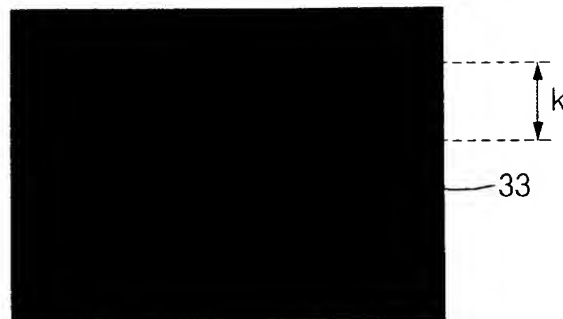


Fig.3b  
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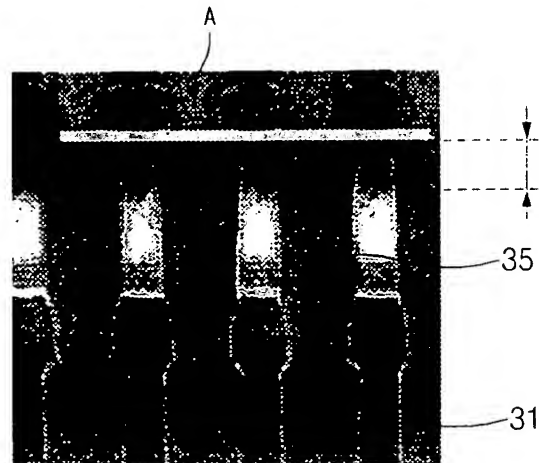


Fig.3c  
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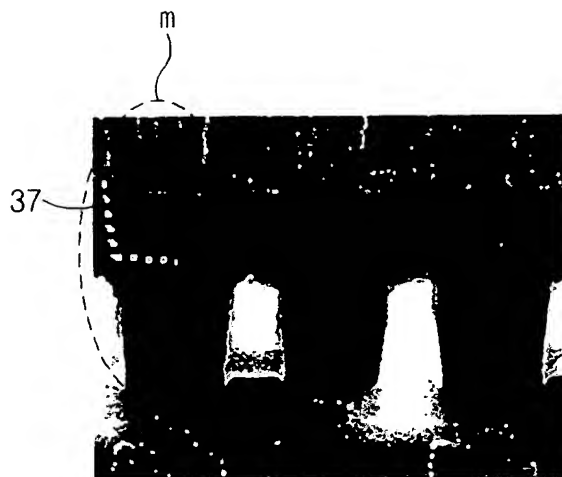


Fig.3d  
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Jung Taik CHEONG et al.  
"Method for Forming A Semiconductor Device with a Hard Mask Layer  
Formed Over a Bit Line to..."  
Applic. No. 10/608,426

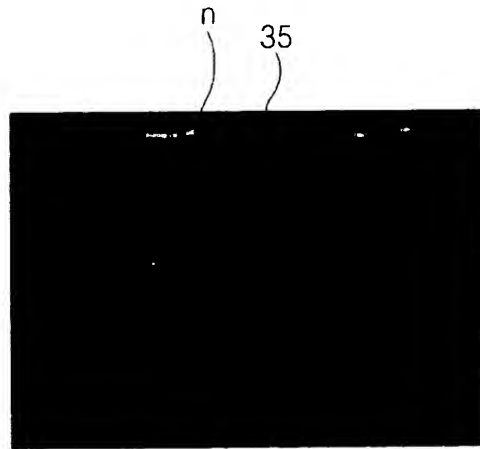


Fig. 3e  
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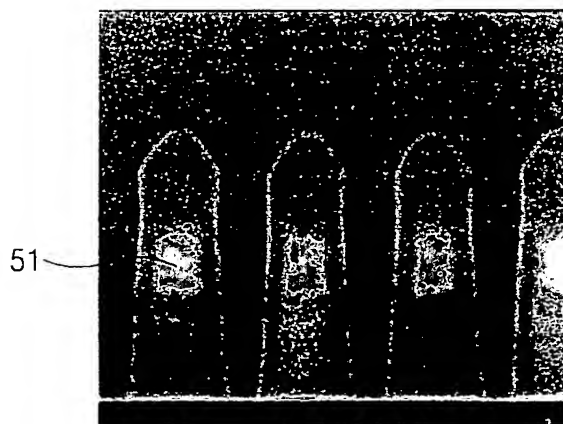


Fig.4d



Fig.4e